

Fig. 4-14 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The constant laser power is 3W. The scan speed is 5cm/sec, the substrate had to be broken under the buffer layer

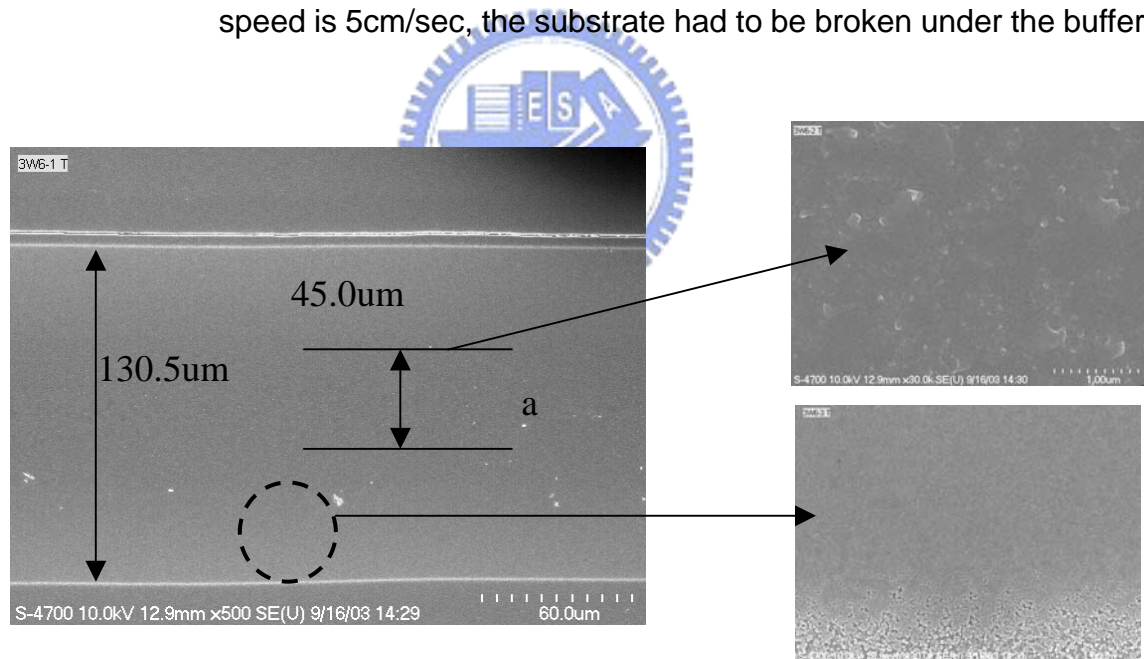


Fig. 4-15 SEM micrographs of CW laser crystallized poly-silicon films after Secco etching for 60sec treatment. The constant laser power is 3W. The scan speed is 6cm/sec, the grain size of area "a" is about 0.6μm